

CHALLENGE 557-HT

SLURRY ADDITIVE FOR CERIUM AND ALUMINUM OXIDE POLISHING SLURRIES

CHALLENGE 557-HT is an aqueous based slurry additive designed to be added to cerium oxide and aluminum oxide polishing slurries. The nature of polishing slurries and their sub-micron particle sizes creates post-polish cleaning issues. High precision optical parts may be polished to the correct specifications using standard slurries but cleaning the slurry particles from the surface of the parts is difficult and can result in damaged or rejected parts. Adding CHALLENGE 557-HT to the polishing slurry allows for that slurry to be more easily cleaned from the glass or ceramic surface. Also, CHALLENGE 557-HT eliminates staining issues and burnishing marks. CHALLENGE 557-HT may also be used with other polishing slurries for similar results.

Typical Applications:

Polishing applications using cerium oxide and aluminum oxide slurries for Precision Optics, Ophthalmic Lenses, Flat Panel Display materials, Glass Disks, and other precision polished parts.

Benefits:

- Better dispersions
- Eliminates staining
- Less sub-surface damage
- Easier post-polish cleaning
- Non-corrosive to machine

Typical Properties:

pH	13.0
Conductivity Ms	16.5
Specific Gravity	1.02

CHALLENGE 557-HT is also available with a neutral pH (CHALLENGE 557-HT-7) and a pH of 10 (CHALLENGE 557-HT-10).

Directions:

CHALLENGE 557-HT is used at a concentration of between 2-3% by volume of slurry. Add CHALLENGE 557-HT to the pre-mixed slurry. The slurry will be ready for immediate use.

Additional Information:

CHALLENGE Products are available in 5-gallon pails and 55-gallon drums, F.O.B. Bethel, Connecticut, and also include: grinding fluids, sawing fluids, lapping/polishing slurry additives, rinse/wet storage additives and ultrasonic/megasonic detergents. Safety Data Sheets available upon request.